

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Toshiyuki OGATA, et al.

Appln. No.: NOT YET ASSIGNED

Confirmation No.: NOT YET ASSIGNED

Group Art Unit: NOT YET ASSIGNED

Filed: August 07, 2001

Examiner: NOT YET ASSIGNED

For: POSITIVE RESIST COMPOSITION AND BASE MATERIAL CARRYING LAYER OF  
THE POSITIVE RESIST COMPOSITION

**PRELIMINARY AMENDMENT**

Commissioner for Patents  
Washington, D.C. 20231

Sir:

Prior to examination, please amend the above-identified application as follows:

**IN THE CLAIMS:**

**Please enter the following amended claims:**

10. A base material comprising:

an organic polymer layer as a first layer formed on a substrate; and

a second resist layer formed on said organic polymer layer, said second resist layer being

composed of a positive resist composition according to claim 1 and having a thickness of from

50 to 200 nm.